REMARKS

Claim 1 and claim 12 are amended by deleting the wording "atomic ratio of O:N is in the interval from 65:35 to 0:100" and introducing the wording "the nitrogen content given as atomic ratio of O:N is higher than 65:35" in order to clarify the differences between the material of the invention and the material of *Sterzel*. Certain obvious typographical errors have also been corrected. Further, it is clarified that the material of the invention is given its special mechanical and physical properties by the high nitrogen content (which previously has not been possible to provide); i.e. the substitution of oxygen with nitrogen. However, as shown by all examples in the description, the glass material of the invention still comprises some oxygen, i.e. it has not yet been possible to exclude oxygen completely, even though this of course is desired.

This amendment has support in the description page 6, line 16-17.

Sterzel discloses amorphous silicon nitride. A conventional process using molecules in gaseous phase is used, whereby reaction with nitrogen-containing molecules is performed in order to provide an amorphous powder. Thus, the resulting material of this process is completely different compared to the invention, in which a nitride glass is produced.

A physical feature of a glass material in the sense of the present invention is that it has a glass transition temperature, across which the glass material can be transferred in a reversible manner.

To the contrary, an amorphous powder (like in *Sterzel*) crystallises in an irreversible manner.

Sterzel discloses (column 3, line 10-14) that the synthesis and handling procedure is completely absent of water and atmospheric oxygen. Furthermore, the material is allowed to crystallize.

In the present invention the amount of nitrogen is maximised (vs the amount of oxygen), in order to obtain e.g. hardness values as high as possible. This is performed in a process, which according to the presented examples involves presence of both oxygen and nitrogen. Further, since the material of the invention is allowed to pass glass transition temperature, the process is reversible.

Thus, even though *Sterzel* refers to a "glass material" it is a completely different material compared to the present invention.

Further, *Sterzel* discloses that the presence of silicon oxide (column 3, line 10-14) at the powder surface "presents problems", whereas in the present invention it is disclosed that the presence of silicon oxide is preferred during manufacturing of the nitride glass (page 5, line 6-10).

Moreover, *Sterzel* discloses silicon nitride powder, in which silicon is partly replaced by another element (not oxygen). Hence, the material according to *Sterzel* does not include oxygen, which is in contrast to the present invention. This difference further demonstrates the different physio-chemical properties of the material of the invention and the material of Sterzel, i.e. a glass and a powder, respectively.

Hence, it is submitted that *Sterzel* refers to a different material compared to the present invention, as well as a different process for obtaining the process, thereby resulting in another material. Thus, the present claims should be allowable in view of *Sterzel*.

In the event there are any questions concerning this Amendment, or the application in general, the Examiner is respectfully urged to telephone the undersigned so that prosecution of the application may be expedited.

Respectfully submitted,

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